

2025 EUVL and Source Workshop

June 21- June 26, 2025

*June 21- 22 (Online Short Courses) &
June 23-26 (In-Person only at MIT Lincoln Laboratory)*

 **LINCOLN LABORATORY**
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Agenda Outline

The agenda outline is provided to allow participants to plan their travel for the 2025 Extreme Ultraviolet Lithography (EUVL) and Source Workshop, which will be held at the MIT Lincoln Laboratory, in Lexington, MA from June 21-26, 2025. A final agenda will be published after the abstract submission date of March 21, 2025. Travel and logistics information will be published on the website www.euvlitho.com by February 2025. For issues concerning logistics or any other questions, please do not hesitate to contact us at info@euvlitho.com.

- June 21 (8 AM – 5 PM): Short Course: EUV and Soft X-ray Sources (Online Only)
- June 22 (8 AM – 5 PM): Short Course: EUV Lithography (Online Only)
 - Description for the short courses will be published during February 2025
- June 23 (8 AM – 4 PM): Blue - X Technical Working Group Meeting (Open to Blue- X TWG Members Only)
- June 23 (4:30 PM - 6 PM): Joint Welcome Reception – Blue-X TWG and 2025 EUVL and Source Workshop Attendees
- June 24 (8 AM – 5 PM): Technical Sessions
- June 25 (8 AM – 5 PM): Technical Sessions
- June 25 (5 PM – 7 PM): Poster Session and Reception
- June 26 (8 AM – 5 PM): Technical Sessions
- June 26 (5 PM – 7 PM): Workshop Dinner